



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of: Wilk et al.

Provisional Serial No.: 60/063,010

Docket: Examiner: TI-24742

Serial No.:

TBD

Art Unit:

TBD TBD

Provisional Filed:

10/23/97

Filed:

Herewith

For:

Low Temperature Method for Forming a Thin, Uniform Oxide

PRELIMINARY AMENDMENT

MAILING CERTIFICATE UNDER 37 CFR § 1.8

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Assistant Commissioner for Patents, Washington,

DC 20231 on

September 28, 1998

Ass't Commissioner for Patents Washington, DC 20231

Examiner:

Prior to examination and calculation of fees, please amend the above-identified application

as follows:

IN THE SPECIFICATION:

On Page 1, lines 5-9, delete the table in its entirety and replace with the following:

Filing

Date 7/31/97

Title

Method For Thin Film Deposition On Single-Crystal

Semiconductor Substrates

60/063,010 10/23/97

Low Temperature Method for Forming a Thin, Uniform

Oxide

On Page 1, lines 14-19, delete the table in its entirety and replace with the following:

Filing

Date 7/31/97

Appl. No. 08/904,009

Method For Thin Film Deposition On Single-Crystal

Semiconductor Substrates